

[Designation of Document] Abstract

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[Problem] To provide a positive resist composition ensuring small line-edge roughness even in fine patterning and wide defocus latitude to patterns of various types, whether sparse or dense type, and whether line or trench type.

[Means for Resolution] A positive resist composition which contains:

(A) a resin containing at least one kind of acrylate derivative repeating units, repeating units having lactone structures and repeating units having hydroxy group-substituted adamantane structures, having a glass transition temperature in the range of 70 to 150°C and capable of increasing its solubility in an alkali developer under action of an acid,

(B) a compound capable of generating an acid upon irradiation with an actinic ray or radiation, and

(C) a mixed solvent containing at least one solvent selected from a propylene glycol monoalkyl ether carboxylate, an alkyl lactate or a linear ketone, and a cyclic ketone.

[Selected Drawing] Nothing